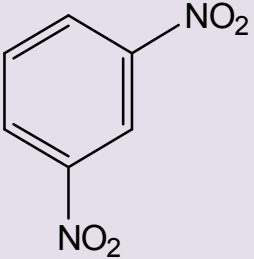
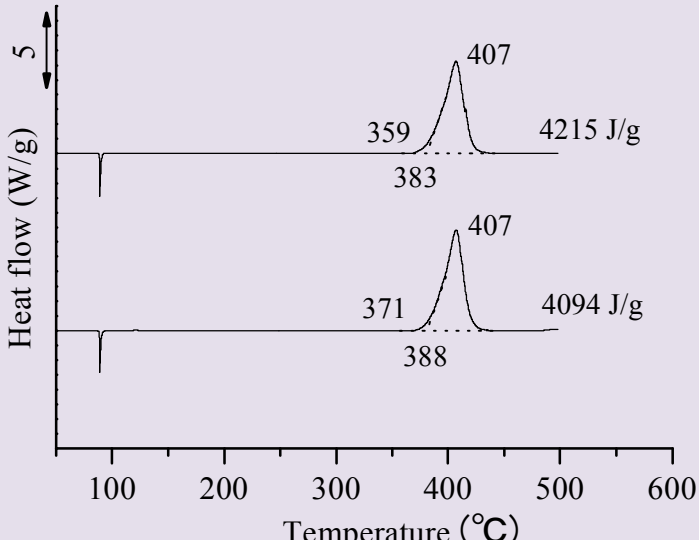
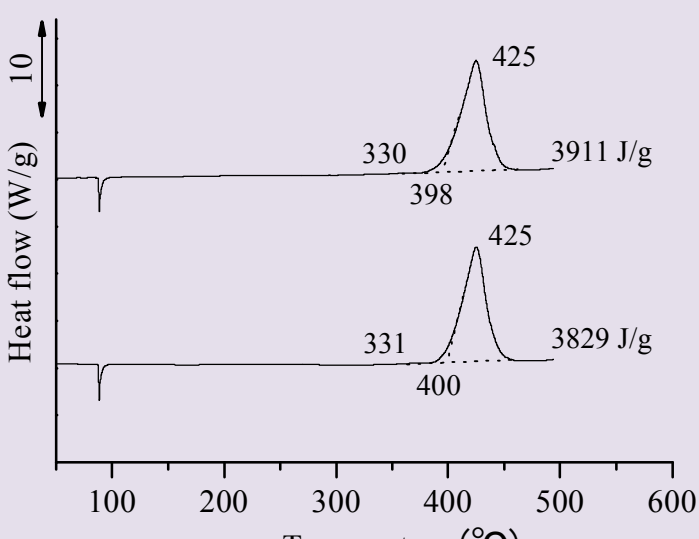
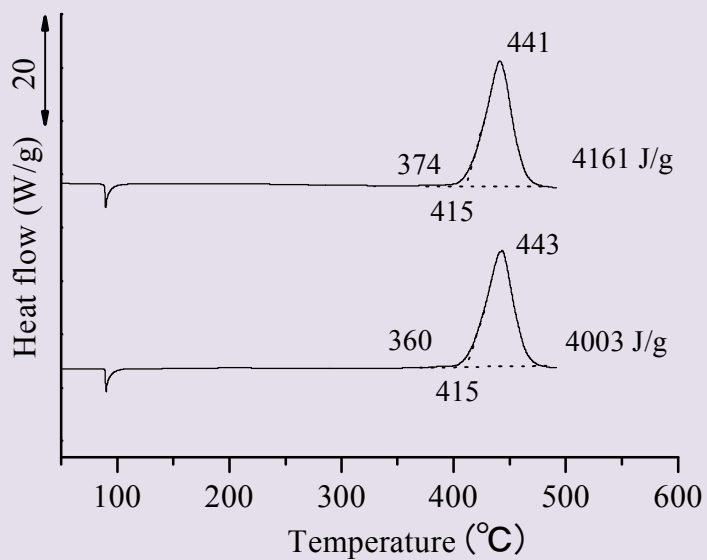


m-dinitrobenzene	$C_6H_4(NO_2)_2$ DNB
	DSC device: SII DSC 7020 SII Nano Technology Inc. dT/dt: 2, 5, 10, 20 K/min Atmosphere: Air Vesel: pressure vessel (SUS) SII Nano Technology Inc. Sample: Wako (> 99.0%)
a) 2 K/min <span style="float: right;">Wako: 和光純薬工業株式会社</span>	
	<Average> $T_a$ : 365 °C $T_o$ : 386 °C $T_{top}$ : 407 °C $Q_{DSC}$ : 4155 J/g
b) 5 K/min	
	<Average> $T_a$ : 331 °C $T_o$ : 399 °C $T_{top}$ : 425 °C $Q_{DSC}$ : 3870 J/g

c) 10 K/min



< Average >

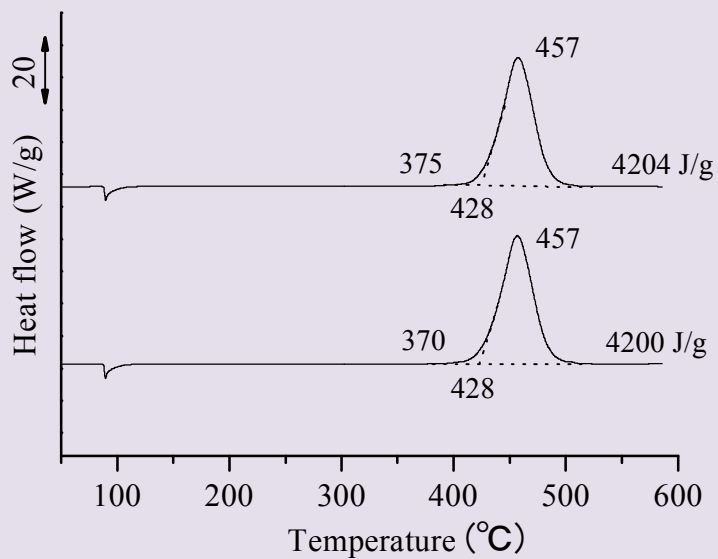
$T_a$  : 367 °C

$T_o$  : 415 °C

$T_{top}$  : 442 °C

$Q_{DSC}$  : 4082 J/g

d) 20 K/min



< Average >

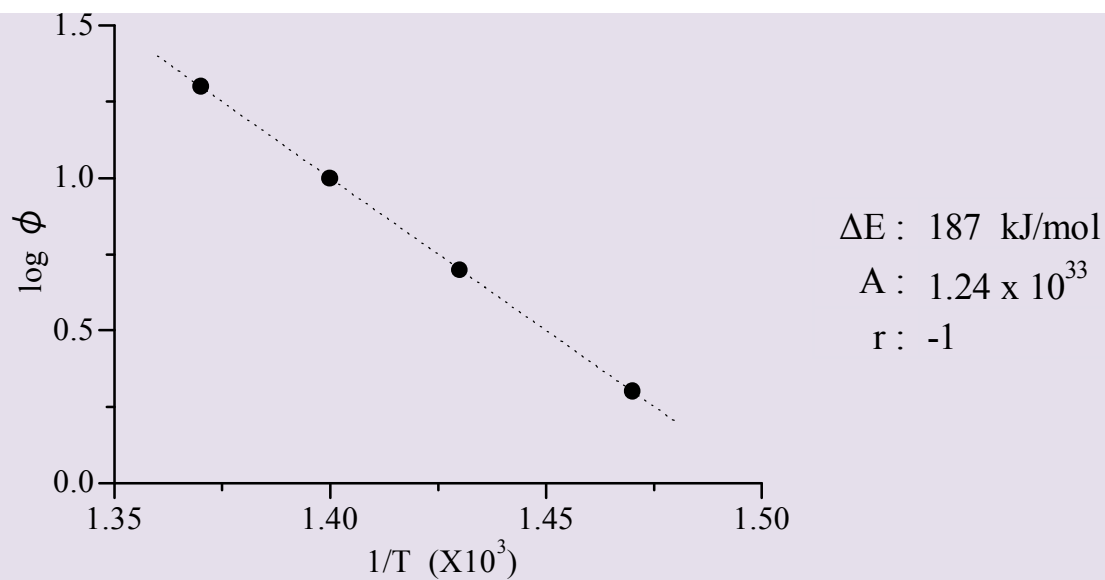
$T_a$  : 373 °C

$T_o$  : 428 °C

$T_{top}$  : 457 °C

$Q_{DSC}$  : 4202 J/g

## ASTM PLOT



Heat rate $\phi$ (K/min)	$T_{\text{peak}}$ (°C)	$T_m$ (K)	$1/T_m \cdot 10^3$	$\log \phi$
2	407	680	1.47	0.301
	407	680	1.47	0.301
5	425	698	1.43	0.699
	425	698	1.43	0.699
10	441	714	1.40	1.00
	443	716	1.40	1.00
20	457	730	1.37	1.30
	457	730	1.37	1.30